



IPW

IBM Docket No. FIS920030147US1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: **Glenn Biery et al.**

Serial No.: **10/605,260**

Date: **June 10, 2005**

Filed: **September 18, 2003**

Group Art Unit: **2891**
Batch No.:

Title: **TWO-MASK PROCESS FOR METAL-
INSULATOR-METAL CAPACITORS AND SINGLE
MASK PROCESS FOR THIN FILM RESISTORS**

Examiner: **Igwe U. Anya**

DeLIO & PETERSON, LLC
121 Whitney Avenue
New Haven, CT 06510-1241

LETTER TO OFFICIAL DRAFTSMAN

Mail Stop ISSUE FEE
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Applicants are herewith submitting **10** sheets of Formal Drawings for the approval of the Draftsman.

Please charge the Assignee IBM Corporation Deposit Account No. **09-0458** for any fee related to the acceptance of the attached Formal Drawings. A duplicate copy of this letter is enclosed for that purpose.

Respectfully submitted,

BY: 

Attorney: **Robert Curcio**
Registration No. **44,638**
(203) 787-0595

ibmf100387000ltrfdrft